

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

	,	CCT 202003
ENVIRONMENT	)	
AND AC OR DC PLASMA	)	RECEIVED
ETCHING OR SUBSTRATES IN	Ó	DES
ENERGY ELECTRON ENHANCED	)	
METHOD AND APPARATUS FOR	)	
	j	
May 15, 2001	)	Docket No. 062002-1751
No.: 09/855,972	)	Examiner: Hassanzadeh, Parviz
Martin, et al.	)	Group Art Unit: 1763
Application of:	)	
	No.: 09/855,972  May 15, 2001  METHOD AND APPARATUS FOR ENERGY ELECTRON ENHANCED ETCHING OR SUBSTRATES IN AND AC OR DC PLASMA	Martin, et al.  No.: 09/855,972  May 15, 2001  METHOD AND APPARATUS FOR ENERGY ELECTRON ENHANCED ETCHING OR SUBSTRATES IN AND AC OR DC PLASMA  )

Mail Stop: Non-Fee Amendment Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

Please enter the following preliminary amendment prior to the examination of the above-identified application.

It is not believed that extensions of time or fees for net addition of claims are required, beyond those, which may otherwise be provided for in documents accompanying this paper. However, in the event that additional extensions of time are necessary to allow consideration of this paper, such extensions are hereby petitioned under 37 C.F.R. § 1.136(a), and any fees required therefor (including fees for net addition of claims) are hereby authorized to be charged to Deposit Account No. 20-0778.